

# Jer-Chyi Wang

## List of Publications by Year in descending order

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82  
papers

696  
citations

516710

16  
h-index

642732

23  
g-index

83  
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docs citations

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times ranked

833  
citing authors

#	ARTICLE	IF	CITATIONS
1	Submillimeter-Scaled PEDOT:PSS/PPy Piezoresistive Pressure Sensor Array and Its Applications in Biomedicine. <i>IEEE Sensors Journal</i> , 2022, 22, 6418-6425.	4.7	10
2	Antiferroelectric titanium-doped zirconia thin films deposited via HiPIMS for highly efficient electrocaloric applications. <i>Journal of the European Ceramic Society</i> , 2021, 41, 3387-3396.	5.7	7
3	Modeling electrical conduction in resistive-switching memory through machine learning. <i>AIP Advances</i> , 2021, 11, .	1.3	2
4	Reaction-inhibited interfacial coating between PEDOT:PSS sensing membrane and ITO electrode for highly-reliable piezoresistive pressure sensing applications. <i>Journal of the Taiwan Institute of Chemical Engineers</i> , 2021, 126, 297-306.	5.3	4
5	N-butylamine-modified graphite nanoflakes blended in ferroelectric P(VDF-TrFE) copolymers for piezoelectric nanogenerators with high power generation efficiency. <i>European Polymer Journal</i> , 2021, 159, 110754.	5.4	4
6	Nanoscale Multidimensional Pd/TiO <sub>2</sub> /g-C <sub>3</sub> N <sub>4</sub> Catalyst for Efficient Solar-Driven Photocatalytic Hydrogen Production. <i>Catalysts</i> , 2021, 11, 59.	3.5	10
7	Highly Reliable Electrocaloric Behaviors of Antiferroelectric Al:ZrO <sub>2</sub> , Thin Films for Solid-State Cooling in Integrated Circuits. <i>IEEE Transactions on Electron Devices</i> , 2021, , 1-7.	3.0	2
8	Robust sandwiched fluorinated graphene for highly reliable flexible electronics. <i>Applied Surface Science</i> , 2020, 499, 143839.	6.1	11
9	Trifluoroethylene bond enrichment in P(VDF-TrFE) copolymers with enhanced ferroelectric behaviors by plasma fluorination on bottom electrode. <i>Journal of the Taiwan Institute of Chemical Engineers</i> , 2020, 107, 152-160.	5.3	2
10	Memristors: Compacted Self-Assembly Graphene with Hydrogen Plasma Surface Modification for Robust Artificial Electronic Synapses of Gadolinium Oxide Memristors ( <i>Adv. Mater. Interfaces</i> ) Tj ETQq0 0 0 rgBT /Overlock 10 Tf 50 377		
11	Real-Time Intraoperative Pressure Monitoring to Avoid Surgically Induced Localized Brain Injury Using a Miniaturized Piezoresistive Pressure Sensor. <i>ACS Omega</i> , 2020, 5, 29342-29350.	3.5	8
12	Layer-dependent solvent vapor annealing on stacked ferroelectric P(VDF-TrFE) copolymers for highly efficient nanogenerator applications. <i>Polymer</i> , 2020, 204, 122822.	3.8	7
13	Analytical modeling electrical conduction in resistive-switching memory through current-limiting-friendly combination frameworks. <i>AIP Advances</i> , 2020, 10, 085117.	1.3	4
14	Compacted Self-Assembly Graphene with Hydrogen Plasma Surface Modification for Robust Artificial Electronic Synapses of Gadolinium Oxide Memristors. <i>Advanced Materials Interfaces</i> , 2020, 7, 2000860.	3.7	6
15	Dimensionally anisotropic graphene with high mobility and a high on/off ratio in a three-terminal RRAM device. <i>Materials Chemistry Frontiers</i> , 2020, 4, 1756-1763.	5.9	9
16	Enhanced piezoelectric tactile sensing behaviors of high-density and low-damage CF <sub>4</sub> -plasma-treated IGZO thin-film transistors coated by P(VDF-TrFE) copolymers. <i>Sensors and Actuators A: Physical</i> , 2020, 304, 111855.	4.1	2
17	A Fluorographene-Based Synaptic Transistor. <i>Advanced Materials Technologies</i> , 2019, 4, 1900422.	5.8	30
18	Miniaturized Flexible Piezoresistive Pressure Sensors: Poly(3,4-ethylenedioxythiophene):Poly(styrenesulfonate) Copolymers Blended with Graphene Oxide for Biomedical Applications. <i>ACS Applied Materials &amp; Interfaces</i> , 2019, 11, 34305-34315.	8.0	32

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19	Damage-Free ALD Blocking Oxide Layer on Functionalized Graphene Nanosheets as Nonvolatile Memories. <i>IEEE Transactions on Electron Devices</i> , 2019, 66, 1113-1117.	3.0	2
20	Multilevel resistive switching behaviors of N <sub>2</sub> -plasma-treated stacked GdO <sub>x</sub> /SiN <sub>x</sub> RRAMs. <i>Japanese Journal of Applied Physics</i> , 2019, 58, SBBB13.	1.5	4
21	Nonlinear resistive switching features of rapid-thermal-annealed aluminum nitride dielectrics with modified charge trapping behaviors. <i>Microelectronic Engineering</i> , 2019, 216, 111033.	2.4	11
22	Nb2O5 and Ti-Doped Nb2O5 Charge Trapping Nano-Layers Applied in Flash Memory. <i>Nanomaterials</i> , 2018, 8, 799.	4.1	2
23	Programmable Synaptic Metaplasticity and below Femtojoule Spiking Energy Realized in Graphene-Based Neuromorphic Memristor. <i>ACS Applied Materials &amp; Interfaces</i> , 2018, 10, 20237-20243.	8.0	71
24	Interface Modification of Bernal- and Rhombohedral-Stacked Trilayer-Graphene/Metal Electrode on Resistive Switching of Silver Electrochemical Metallization Cells. <i>ACS Applied Materials &amp; Interfaces</i> , 2017, 9, 37031-37040.	8.0	4
25	Cross-Talk Immunity of PEDOT:PSS Pressure Sensing Arrays with Gold Nanoparticle Incorporation. <i>Scientific Reports</i> , 2017, 7, 12252.	3.3	12
26	Effects of bottom electrode on resistive switching of silver programmable metallization cells with Gd <sub>x</sub> O <sub>y</sub> /Al <sub>x</sub> O <sub>y</sub> solid electrolytes. <i>Vacuum</i> , 2017, 140, 30-34.	3.5	7
27	Integration of ammonia-plasma-functionalized graphene nanodiscs as charge trapping centers for nonvolatile memory applications. <i>Carbon</i> , 2017, 113, 318-324.	10.3	22
28	Graphene nanodots with high-k dielectrics for flash memory applications. , 2017, , .		0
29	Data Retention Characterization of Gate-Injected Gold-Nanoparticle Non-Volatile Memory with Low-Damage CF4-Plasma-Treated Blocking Oxide Layer. <i>Nanomaterials</i> , 2017, 7, 385.	4.1	1
30	Nitrogen Plasma Surface Modification of Poly(3,4-ethylenedioxythiophene):Poly(styrenesulfonate) Films To Enhance the Piezoresistive Pressure-Sensing Properties. <i>Journal of Physical Chemistry C</i> , 2016, 120, 25977-25984.	3.1	19
31	Monolayer MoS2 for nonvolatile memory applications. , 2016, , .		0
32	Low-damage NH <sub>3</sub> plasma treatment on SiO <sub>2</sub> tunneling oxide of chemically-synthesized gold nanoparticle nonvolatile memory. <i>Current Applied Physics</i> , 2016, 16, 605-610.	2.4	5
33	Analysis of current compliance on resistive switching of silver programmable metallization cells with stacked SiO <sub>x</sub> /SiO <sub>2</sub> solid electrolytes. , 2015, , .		0
34	Thickness-Optimized Multilevel Resistive Switching of Silver Programmable Metallization Cells With Stacked SiO <sub>x</sub> /SiO <sub>2</sub> Solid Electrolytes. <i>IEEE Transactions on Electron Devices</i> , 2015, 62, 1478-1483.	3.0	5
35	Charge storage characteristics of nonvolatile memories with chemically-synthesized and vacuum-deposited gold nanoparticles. <i>Current Applied Physics</i> , 2015, 15, 535-540.	2.4	4
36	Ultra-large resistance ratio of silver programmable metallization cell with stacked silicon oxide films. <i>Vacuum</i> , 2015, 118, 80-84.	3.5	3

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37	Thickness dependence of Al <sub>2</sub> O <sub>3</sub> /HfO <sub>2</sub> /Al <sub>2</sub> O <sub>3</sub> stacked tunneling layers on gadolinium oxide nanocrystal nonvolatile memory. <i>Microelectronic Engineering</i> , 2015, 138, 52-56.	2.4	2
38	Characterization of Piezoresistive PEDOT:PSS Pressure Sensors with Inter-Digitated and Cross-Point Electrode Structures. <i>Sensors</i> , 2015, 15, 818-831.	3.8	37
39	Light-Addressable Potentiometric Sensor with Nitrogen-Incorporated Ceramic Sm <sub>2</sub> O <sub>3</sub> Membrane for Chloride Ions Detection. <i>Journal of the American Ceramic Society</i> , 2015, 98, 443-447.	3.8	17
40	Total ionizing dose (TID) effects of <sup>60</sup> Co ray radiation on switching behaviors of Ag/AlO <sub>x</sub> /Pt RRAM device. <i>Nanoscale Research Letters</i> , 2014, 9, 452.	5.7	34
41	Performance improvement of gadolinium oxide resistive random access memory treated by hydrogen plasma immersion ion implantation. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2014, 32, .	2.1	4
42	Oxygen plasma immersion ion implantation treatment to enhance data retention of tungsten nanocrystal nonvolatile memory. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2014, 32, 02B112.	2.1	1
43	High-Performance Multilevel Resistive Switching Gadolinium Oxide Memristors With Hydrogen Plasma Immersion Ion Implantation Treatment. <i>IEEE Electron Device Letters</i> , 2014, 35, 452-454.	3.9	18
44	Effects of charge storage dielectric thickness on hybrid gadolinium oxide nanocrystal and charge trapping nonvolatile memory. <i>Current Applied Physics</i> , 2014, 14, 232-236.	2.4	9
45	Ambipolar carrier injection of gold nanocrystal nonvolatile memory with different tunneling oxide thickness. , 2014, , .		0
46	Retention behavior of graphene oxide resistive switching memory on flexible substrate. , 2013, , .		4
47	Platinum-aluminum alloy electrode for retention improvement of gadolinium oxide resistive switching memory. <i>Applied Physics A: Materials Science and Processing</i> , 2013, 113, 37-40.	2.3	7
48	Nano-IGZO layer for EGFET in pH sensing characteristics. , 2013, , .		5
49	Robust nitrogen plasma immersion ion implantation treatment on gadolinium oxide resistive switching random access memory. , 2013, , .		0
50	Yield improvement of gadolinium oxide resistive switching memory with oxygen post-metallization annealing. , 2013, , .		1
51	Multilevel ultra-fast and disturb-free flash memory with double embedded Au and Gd <sub>2</sub> O <sub>3</sub> nanocrystals. , 2013, , .		0
52	High performance gadolinium oxide nanocrystal memory with optimized charge storage and blocking dielectric thickness. , 2013, , .		1
53	LAPS with nanoscaled and highly polarized HfO <sub>2</sub> by CF <sub>4</sub> plasma for NH <sub>4</sub> <sup>+</sup> detection. <i>Sensors and Actuators B: Chemical</i> , 2013, 180, 71-76.	7.8	24
54	Characterization of gadolinium oxide thin films with CF <sub>4</sub> plasma treatment for resistive switching memory applications. <i>Applied Surface Science</i> , 2013, 276, 497-501.	6.1	21

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55	Zero interface dipole induced threshold voltage shift of HfO <sub>2</sub> /SiO <sub>2</sub> gate dielectric stacks with NH <sub>3</sub> plasma treatment. <i>Microelectronic Engineering</i> , 2013, 109, 120-122.	2.4	0
56	Superior Improvements in GIDL and Retention by Fluorine Implantation in Saddle-Fin Array Devices for Sub-40-nm DRAM Technology. <i>IEEE Electron Device Letters</i> , 2013, 34, 1124-1126.	3.9	8
57	Hybrid polarity and carrier injection of gold and gadolinium oxide bi-nanocrystals structure. <i>Applied Physics Letters</i> , 2013, 102, 083507.	3.3	2
58	Performance Revelation and Optimization of Gold Nanocrystal for Future Nonvolatile Memory Application. <i>Japanese Journal of Applied Physics</i> , 2013, 52, 04CJ09.	1.5	3
59	Low-Power and High-Reliability Gadolinium Oxide Resistive Switching Memory with Remote Ammonia Plasma Treatment. <i>Japanese Journal of Applied Physics</i> , 2013, 52, 04CD07.	1.5	6
60	Tunable bandgap energy of fluorinated nanocrystals for flash memory applications produced by low-damage plasma treatment. <i>Nanotechnology</i> , 2012, 23, 475201.	2.6	6
61	Characteristics of plasma immersion ion implantation treatment on tungsten nanocrystal nonvolatile memory. <i>Solid-State Electronics</i> , 2012, 77, 31-34.	1.4	1
62	Charge storage and data retention characteristics of forming gas-annealed Gd <sub>2</sub> O <sub>3</sub> -nanocrystal nonvolatile memory cell. <i>Microelectronics Reliability</i> , 2012, 52, 1627-1631.	1.7	3
63	Gadolinium-based metal oxide for nonvolatile memory applications. <i>Microelectronics Reliability</i> , 2012, 52, 635-641.	1.7	16
64	Gadolinium oxide nanocrystal nonvolatile memory with HfO <sub>2</sub> /Al <sub>2</sub> O <sub>3</sub> nanostructure tunneling layers. <i>Nanoscale Research Letters</i> , 2012, 7, 177.	5.7	9
65	CF <sub>4</sub> plasma treatment on nanostructure band engineered Gd <sub>2</sub> O <sub>3</sub> -nanocrystal nonvolatile memory. <i>Journal of Applied Physics</i> , 2011, 109, 064506.	2.5	21
66	Functionalization of nanoscaled 2 nm-thick ALD-HfO <sub>2</sub> layer by rapid thermal annealing and CF <sub>4</sub> plasma for LAPS NH <sub>3</sub> detection. , 2011, , .		0
67	Effects of a HfMoN Metal Gate and Self-Aligned Fluorine-Ion Implantation on the Negative-Bias Temperature Instability of pMOSFETs With $\text{HfO}_2/\text{SiO}_2$ Gate Dielectrics. <i>IEEE Electron Device Letters</i> , 2011, 32, 1017-1019.	3.9	0
68	Dual-sputtered process sensitivity of HfGdO charge-trapping layer in SONOS-type nonvolatile memory. <i>Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics</i> , 2011, 29, 011009.	1.2	4
69	Characterization of K <sup>+</sup> and Na <sup>+</sup> -Sensitive Membrane Fabricated by CF <sub>4</sub> Plasma Treatment on Hafnium Oxide Thin Films on ISFET. <i>Journal of the Electrochemical Society</i> , 2011, 158, J91.	2.9	19
70	Zero Dipole Formation at HfGdO/SiO <sub>2</sub> Interface by Hf/Gd Dual-Sputtered Method. <i>Journal of the Electrochemical Society</i> , 2011, 158, H502.	2.9	8
71	Effects of HfO <sub>2</sub> trapping layer in Gd <sub>2</sub> O <sub>3</sub> /HfO <sub>2</sub> /SiO <sub>2</sub> nanocrystal nonvolatile memory with multi-tunneling layers. , 2011, , .		0
72	Highly sensitivity of potassium ion detection realized on fluorinated-HfO <sub>2</sub> by fluorine implantation on EIS. , 2011, , .		0

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73	Effects of CF <sub>4</sub> Plasma Treatment on pH and pNa Sensing Properties of Light-Addressable Potentiometric Sensor with a 2-nm-Thick Sensitive HfO <sub>2</sub> Layer Grown by Atomic Layer Deposition. Japanese Journal of Applied Physics, 2011, 50, 04DL06.	1.5	7
74	Improved characteristics of Gd <sub>2</sub> O <sub>3</sub> nanocrystal memory with substrate high- $\epsilon$ -low junction. Solid-State Electronics, 2010, 54, 1493-1496.	1.4	6
75	Characteristics optimization of N <sub>2</sub> O annealing on tungsten nanocrystal with W/Si dual-sputtered method for nonvolatile memory application. Microelectronics Reliability, 2010, 50, 639-642.	1.7	3
76	Improvements of Fermi-level pinning and NBTI by fluorinated HfO <sub>2</sub> . , 2010, , .		0
77	Fluorinated CMOS HfO <sub>2</sub> for high performance (HP) and low stand-by power (LSTP) application by pre- and post-CF <sub>4</sub> plasma passivation. , 2010, , .		0
78	Nanostructure band engineering of gadolinium oxide nanocrystal memory by CF <sub>4</sub> plasma treatment. Applied Physics Letters, 2010, 97, 023513.	3.3	25
79	Characteristics of Gadolinium Oxide Nanocrystal Memory with Optimized Rapid Thermal Annealing. Electrochemical and Solid-State Letters, 2009, 12, H202.	2.2	34
80	Fluorinated HfO <sub>2</sub> gate dielectrics engineering for CMOS by pre- and post-CF <sub>4</sub> plasma passivation. , 2008, , .		7
81	A Highly Reliable Multi-level and 2-bit/cell Operation of Wrapped-Select-Gate (WSG) SONOS Memory with Optimized ONO Thickness. , 2007, , .		0
82	Color Discrimination in Color Vision Deficiency: Photon-Assisted Piezoelectric IGZO Color-Tactile Sensors with P(VDF-TrFE)/Metal-Decorated TiO <sub>2</sub> Nanofibers Nanocomposites. Advanced Materials Technologies, 0, , 2101147.	5.8	1